

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S6	22607	((substrate or wafer) near4 (temperature or heat\$3)) with (measur\$5 or sens\$3 or detect\$3 or determin\$5)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/26 16:19
S7	16287	(substrate or wafer) with (temperature or heat\$3) with ((dimension\$3 near response) or expan\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/26 16:20
S8	272	(substrate or wafer) with (temperature or heat\$3) with ((dimension\$3 near response) or expan\$4) with (calculat\$3 or determin\$5 or predict\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/26 16:21
S9	8971	(substrate or wafer) with (temperature or heat\$3) with ((dimension\$3 near response) or expan\$4) with (calculat\$3 or determin\$5 or predict\$3 or model\$3 or coefficient)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/26 16:23
S10	742	S6 and S9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/26 16:22
S11	2372	(substrate or wafer) with ((dimension\$3 near response) or expan\$4) with (correct\$3 or adjust\$4 or compensat\$3)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/26 16:24
S12	95	S10 and S11	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/26 16:28
S13	82414	(mask or reticle) and (lithography or photolithography or (micro near lithography))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/26 16:30

S15	14	S12 and S13	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/10/26 17:44
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